

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER OF PATENTS AND TRADEMARKS
Washington, D.C. 20231
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/709,483	11/13/2000	Oh-Nam Kwon	8733.307.00	4557	
75	90 01/11/2002				
Steven B Kelber Long Aldridge & Norman LLP 6th Floor			EXAMINER		
			PHAM, THANH V		
701 Pennsylvania Avenue N W Washington, DC 20004			ART UNIT	PAPER NUMBER	
3			2823		
			DATE MAILED: 01/11/2002		

Please find below and/or attached an Office communication concerning this application or proceeding.

		·.	#			
Li Li	Application No.	Applicant(s)				
	09/709,483	KWON, OH-NAM	•			
Office Action Summary	Examiner	Art Unit				
	Thanh V Pham	2823	* .			
The MAILING DATE of this communication ap Period for Reply	p ars on the cover sheet with the	correspondence addre	ss			
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION. Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. If the period for reply specified above is less than thirty (30) days, a replied in NO period for reply is specified above, the maximum statutory period. Failure to reply within the set or extended period for reply will, by statut. Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b). Status	136(a). In no event, however, may a reply be the light of the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from e. cause the application to become ABANDONE	nely filed /s will be considered timely. In the mailing date of this comm D (35 U.S.C. § 133)	unication.			
1) Responsive to communication(s) filed on 23	January <u>2001</u> .	5	*			
<u> </u>	his action is non-final.					
3) Since this application is in condition for allow closed in accordance with the practice under	ance except for formal matters, p	rosecution as to the n 453 O.G. 213.	nerits is			
Disposition of Claims			•			
4) Claim(s) 1-13 is/are pending in the application	n.		•			
4a) Of the above claim(s) is/are withdra	wn from consideration.		•			
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>1-13</u> is/are rejected.			^.			
7) Claim(s) is/are objected to.		• ¹ *				
8) Claim(s) are subject to restriction and/	or election requirement.		r Literatur			
Application Papers						
9) The specification is objected to by the Examine	er.					
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.						
If approved, corrected drawings are required in reply to this Office action.						
12) ☐ The oath or declaration is objected to by the E	xaminer.					
Priority under 35 U.S.C. §§ 119 and 120						
13) Acknowledgment is made of a claim for foreig	n priority under 35 U.S.C. § 119(a	a)-(d) or (f).				
a)⊠ All b)☐ Some * c)☐ None of:			•			
1. Certified copies of the priority documen						
2. Certified copies of the priority documen						
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).						
a) ☐ The translation of the foreign language provisional application has been received. 15)☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.						
Attachment(s)						
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s)	5) Notice of Informal	y (PTO-413) Paper No(s). Patent Application (PTO-1				

Application/Control Number: 09/709,483

Art Unit: 2823

DETAILED ACTION

Claim Objections

1. Claim 11 is objected to because of the following informalities: "Mo Cr" should be --Mo, Cr--. Appropriate correction is required.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- 3. Claims 1-2 and 11 are rejected under 35 U.S.C. 102(a) as being anticipated by Havemann et al. U.S. Patent No. 5,891,804.

Havemann et al. reference discloses a process for forming thin film conductors comprising forming a photoresist pattern 46 on a substrate 44/42/40/30/10; etching a portion of the substrate to form a groove 47 using the photoresist pattern as a mask;

depositing a second metal 50 on the substrate, col. 2, lines 13-15, and a height of the second metal being smaller than a depth of the groove, fig. 3b; removing the photoresist pattern on the substrate and the second metal on the photoresist other than in the grove, fig. 3c; and

forming the first metal 52 principally copper, col. 2, line 18, on the second metal in the groove col. 4, lines 54-55, by electroless plating.

Application/Control Number: 09/709,483

Art Unit: 2823

The step of electroless deposition inherently includes the step of preparing a mixed solution having a reductant and a first metal and submerging the substrate in the mixed solution.

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 4-5, 7-8, 10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Havemann et al. as applied to claims 1-2 and 11 above, and further in view of Senda et al. U.S. Patent No. 5,364,459.

Havemann et al. reference does not disclose Ag and Au and the kind of reductant used. Senda et al. reference discloses in the background of the invention that the first metal could be Cu, Ag or Au; the reductant could be formaldehyde; and "the electroless plating is not only applied to formation of a conductive film such as an electrode for an electronic component", col. 1, lines 10-35. It would have been obvious to one of ordinary skill in the art to apply the known materials as stated by Senda et al. to the method of Havemann et al. because such materials would have been chosen for electroless plating process in the art of making electrode for an electronic device.

6. Claims 3, 6 and 9 are rejected under 35 U.S.C. 103(a) as being unpatentable over Havemann et al. and Senda et al. as applied to claims 1-2, 4-5, 7-8 and 10-11

Application/Control Number: 09/709,483

Art Unit: 2823

official realisations con co, is

above, and further in view of Charneski et al. U.S. Patent No. 6,284,652 B1 and/or Eriksson U.S. Patent No. 3,632,435.

Both Havemann et al. and Senda et al. do not disclose the mixed solution for the electroless plating. Charneski et al. reference discloses sulfuric acid and cupric sulfate used in cooper plating process. Eriksson reference discloses the use of silver nitrate, gold chloride with noble metal salts and hydroxide in the mixed solution for electroless plating. It would have been obvious to one of ordinary skill in the art to apply the known materials as stated by Charneski et al. and/or Eriksson to the method of Havemann et al. and Senda et al. because such materials would have been chosen for the electroless plating process in the art of making electrode for an electronic device in the process of the combination of Havemann et al. and Senda et al.

7. Claims 12-13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Havemann et al. and Senda et al. as applied to claims 1-2, 4-5, 7-8, 10 and 11 above, and further in view of JP 05-265040 and applicant's admitted prior art.

Havemann et al. reference discloses a process for forming thin film conductors comprising forming a photoresist pattern on a substrate using electroless plating, Senda et al. reference discloses formation of a conductive film such as an electrode for an electronic component using electroless plating. None of the references disclose the further steps for forming the transistor. However, JP 05-265040 (provided by applicant) discloses the steps of making gate line in a trench and the applicant admitted prior art that performing the further steps for forming the transistor.

Page 5

Application/Control Number: 09/709,483

Art Unit: 2823

It would have been obvious to one of ordinary skill in the art to apply the gate electrode of Senda et al. using the method of Havemann et al. into JP 05-265040 reference of making a trench gate line and the applicant's admitted prior art of forming transistor as the method and the analogous electrode would be selected in accordance with JP 05-265040 and the applicant's admitted prior art.

Conclusion

- 8. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.
- 9. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thanh V Pham whose telephone number is 703-308-2543. The examiner can normally be reached on M-F (8:30-5:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael M. Fahmy can be reached on 703-308-4918. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 (7724, 3431 and 3432) for regular communications and 703-308-7382 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

TvP

December 13, 2001

Primary Examiner